



**PATENT APPLICATION**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Attn: OIPE

Satoshi INOUE, et al.

Application No.: 10/748,206

Docket No.: 040852.98

Filed: December 31, 2003

For: MANUFACTURING METHOD OF ACTIVE MATRIX SUBSTRATE, ACTIVE MATRIX SUBSTRATE AND LIQUID CRYSTAL DISPLAY

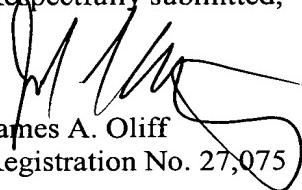
**REQUEST FOR CORRECTION OF PALM RECORDS**

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Sir:

Attached is a photocopy of the original filing receipt on which an error has been corrected in red. This error are being brought to the attention of the Patent and Trademark Office so that it may correct its records.

Respectfully submitted,

  
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JAO:JSA/tje

Date: March 22, 2004

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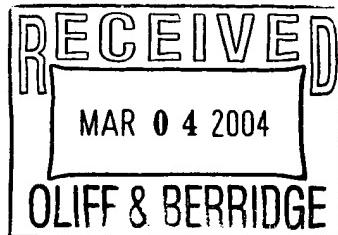


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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY.DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/748,206	12/31/2003	2812	770	040852.98	27	7	1

25944  
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CONFIRMATION NO. 5363  
FILING RECEIPT



\*OC000000011972042\*

Date Mailed: 02/26/2004

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**Applicant(s)**

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Tatsuya Shimoda, Nagano-ken, JAPAN;  
Suwa-shi

**Domestic Priority data as claimed by applicant**

This application is a DIV of 10/263,070 10/03/2002  
which is a REI of 09/113,373 07/10/1998 PAT 6,127,199  
which is a CIP of PCT/JP97/04110 11/11/1997

**Foreign Applications**

JAPAN 8-315590 11/12/1996  
JAPAN 8-327688 11/22/1996

**Projected Publication Date:** None, application is not eligible for pre-grant publication

**Non-Publication Request:** No

**Early Publication Request:** No

**Title**

Manufacturing method of active matrix substrate, active matrix substrate and liquid crystal display

device

**Preliminary Class**

438

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Title 37, Code of Federal Regulations, 5.11 & 5.15**

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